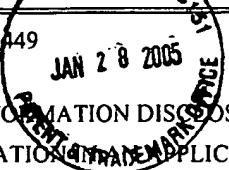



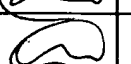




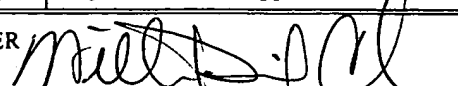




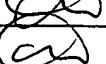



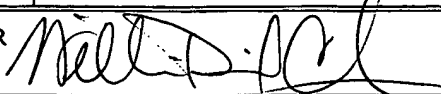
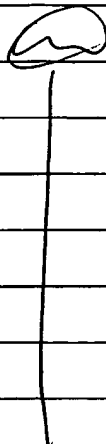







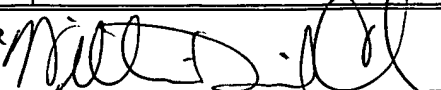
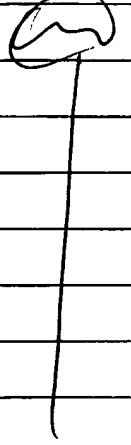







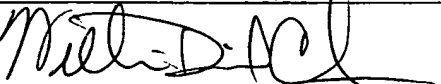



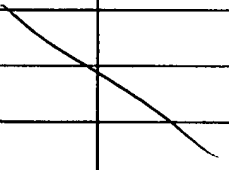


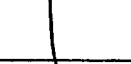




FORM PTO-1449 		DOCKET NUMBER DSI 303	APPLICATION NUMBER 10/816,179 10/815,994				
INFORMATION DISCLOSURE CITATION IN TRADE APPLICATION		APPLICANTS Chung J. Lee and Atul Kumar					
		FILING DATE March 31, 2004	GROUP ART UNIT 1763 2823				
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

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION		APPLICANTS Chung J. Lee and Atul Kumar					
		FILING DATE March 31, 2004		GROUP ART UNIT 4763 2823			
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION		APPLICANTS Chung J. Lee and Atul Kumar					
		FILING DATE March 31, 2004		GROUP ART UNIT 1763 2823			
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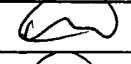


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	6,265,320	07/24/2001	Shi et al.				
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		APPLICANTS Chung J. Lee and Atul Kumar		
		FILING DATE March 31, 2004	GROUP ART UNIT 1763 2823	

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SHEET 1 OF 1

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	APPLICANTS Chung J. Lee and Atul Kumar	
	FILING DATE March 31, 2004	GROUP ART UNIT 2827

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	6,455,443	9/24/02	Eckert et al.			
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